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Docket No.: 055071-0328

<u>PATENT</u>

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Customer Number: 20277

Robert SOCHA, et al.

Confirmation Number: 2388

Application No.: 10/756,829

Group Art Unit: 2825

Filed: January 14, 2004

Examiner: Suresh Memula

For: METHOD OF OPTICAL PROXIMITY CORRECTION DESIGN FOR CONTACT HOLE

MAŞK

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed more than three months after the U.S. filing date AND after the mailing date of the first Office Action on the merits, but before the mailing date of a Final Rejection or Notice of Allowance.

06/19/2007 SSITHIB1 00000074 500417 10756829

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10/756,829

In accordance with 37 CFR 1.17(p), please charge the fee of \$180.00 to Deposit Account No. 500417.

Each English language reference was cited in a corresponding foreign application search report or office action and its relevance discussed therein. A copy of the foreign search report or office action is attached for the Examiner's information.

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

McDERMOTT WILL & EMERY LLP

Please recognize our Customer No. 20277

as our correspondence address.

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Phone: 202.756.8000 DT:llg Facsimile: 202.756.8087 Date: June 18, 2007

SHEET 1 OF 1

INFORMATION DISCLOSURE CITATION IN AN APPLICATION				ATTY. DOCKET NO. 055071-0328			L NO. 56,829			
				APPLICANT Robert John SC	APPLICANT Robert John SOCHA, et al.					
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		J. Fung CHEN, et al., "Practical I-Line OPC Contact Masks for Sub-0.3Micron Design Rule Application: Part 1—OPC Design Optimization," pp 181-201, 1997								
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